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| APPLICATION NO. | FIL | ING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|------------------------|------|------------|----------------------|---------------------|------------------|
| 10/661,051 | 09 | 9/13/2003 | Michael K. Gallagher | 51473 | 6724 |
| 21874 | 7590 | 07/15/2005 | | EXAMINER | |
| EDWARDS P.O. BOX 55 | | ELL, LLP | | CHEN, KI | N CHAN |
| BOSTON, M | - | | | ART UNIT | PAPER NUMBER |
| · | | | | 1765 | |

DATE MAILED: 07/15/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

| | Application No. | Applicant(s) | | | | |
|----------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|------------------------------------------------------------------------------------------------------------------------------------------------------------|----------------------------------------------------------------------------------------------------------------------------------------------|-------------|--|--|--|
| | 10/661,051 | GALLAGHER ET | AL. | | | |
| Office Action Summary | Examiner | Art Unit | | | | |
| | Kin-Chan Chen | 1765 | | | | |
| The MAILING DATE of this communication a Period for Reply | appears on the cover shee | t with the correspondence ac | idress | | | |
| A SHORTENED STATUTORY PERIOD FOR REI THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a - If NO period for reply is specified above, the maximum statutory peri - Failure to reply within the set or extended period for reply will, by sta Any reply received by the Office later than three months after the may earned patent term adjustment. See 37 CFR 1.704(b). | N. 1.136(a). In no event, however, ma reply within the statutory minimum of iod will apply and will expire SIX (6) I state, cause the application to becom | y a reply be timely filed f thirty (30) days will be considered time MONTHS from the mailing date of this c e ABANDONED (35 U.S.C. § 133). | | | | |
| Status | | • | | | | |
| 1)⊠ Responsive to communication(s) filed on 06 | <u> 5 July 2005</u> . | | | | | |
| 2a) ☐ This action is FINAL . 2b) ☑ T | · · · · · · · · · · · · · · · · · · · | | | | | |
| 3) Since this application is in condition for allow |] Since this application is in condition for allowance except for formal matters, prosecution as to the ments is | | | | | |
| closed in accordance with the practice unde | er Ex parte Quayle, 1935 (| C.D. 11, 453 O.G. 213. | | | | |
| Disposition of Claims | | | · | | | |
| 4)⊠ Claim(s) <u>1-18</u> is/are pending in the applicati | | | | | | |
| 4a) Of the above claim(s) 14-18 is/are withd | rawn from consideration. | | | | | |
| 5) Claim(s) is/are allowed. | | | | | | |
| 6)⊠ Claim(s) <u>1-13</u> is/are rejected. 7)□ Claim(s) is/are objected to. | | | | | | |
| 8) Claim(s) are subject to restriction and | d/or election requirement | | | | | |
| | | | | | | |
| Application Papers | | | | | | |
| 9) The specification is objected to by the Exam | | | | | | |
| 10)⊠ The drawing(s) filed on <u>13 September 2003</u> | | | miner. | | | |
| Applicant may not request that any objection to t | - · · | • | ED 4 404(4) | | | |
| Replacement drawing sheet(s) including the corn 11) The oath or declaration is objected to by the | · | | • • | | | |
| Priority under 35 U.S.C. § 119 | Examinor. Note the attac | ned Cinec / tales of femilia | 10 102. | | | |
| 12) Acknowledgment is made of a claim for fore | ian naority under 35 II S (| 2 & 110(a)(d) or (f) | | | | |
| a) All b) Some * c) None of: | ight phonty under 35 0.0. | 3. 8 113(a)-(a) of (i). | | | | |
| 1. Certified copies of the priority docume | ents have been received. | • | | | | |
| 2. Certified copies of the priority docume | | n Application No | | | | |
| 3. Copies of the certified copies of the p | riority documents have be | en received in this National | Stage | | | |
| application from the International Bur | • • • • • • • • • • • • • • • • • • • • | | | | | |
| * See the attached detailed Office action for a | list of the certified copies | not received. | | | | |
| Attachment(s) | | | | | | |
| 1) Notice of References Cited (PTO-892) | 4) 🗍 Intervi | ew Summary (PTO-413) | | | | |
| 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) | Paper | No(s)/Mail Date | 0.450) | | | |
| 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/Paper No(s)/Mail Date 090904; 102904. | (08) 5) ☐ Notice 6) ☐ Other: | of Informal Patent Application (PT | U-152) | | | |
| S. Patent and Trademark Office | | | | | | |

DETAILED ACTION

Election/Restrictions

1. Applicant's election of claims 1-13 in the reply filed on July 6, 2005 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

Drawings

2. The drawings are objected to under 37 CFR 1.83(a). The drawings must show every feature of the invention specified in the claims. Therefore, the A porous overlayer 25 (e.g., on page 21, the second paragraph of specification) and the A porous overlayer 45 (e.g., on page 21, the third paragraph of specification) must be shown. No new matter should be entered.

Corrected drawing sheets in compliance with 37 CFR 1.121(d) are required in reply to the Office action to avoid abandonment of the application. Any amended replacement drawing sheet should include all of the figures appearing on the immediate prior version of the sheet, even if only one figure is being amended. The figure or figure number of an amended drawing should not be labeled as "amended." If a drawing figure is to be canceled, the appropriate figure must be removed from the replacement sheet, and where necessary, the remaining figures must be renumbered and appropriate

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changes made to the brief description of the several views of the drawings for consistency. Additional replacement sheets may be necessary to show the renumbering of the remaining figures. Each drawing sheet submitted after the filing date of an application must be labeled in the top margin as either "Replacement Sheet" or "New Sheet" pursuant to 37 CFR 1.121(d). If the changes are not accepted by the examiner, the applicant will be notified and informed of any required corrective action in the next Office action. The objection to the drawings will not be held in abeyance.

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Besling et al. (US 6,562,732; hereinafter "Besling") in view of Odian (p.18, "Principles of Polymerization", 1981, second edition).

In a method of manufacturing a device, Besling teaches that a sacrificial material layer may be disposed on a device substrate. An overlayer (e.g., porous dielectric) material may be disposed on the sacrificial material layer. The sacrificial material layer may be removed to form an air gap. The sacrificial material layer may

comprise a polymer (abstract; col. 2, lines 34-44; Figures). Besling teaches using a polymer as sacrificial material. The disclosure of Besling is not limited to any type of polymer. In the book of "Principles of Polymerization", Odian teaches that polymers may be linear, branched, or cross-linked polymers (p.18). Hence, it would have been obvious to one with ordinary skill in the art to use a cross-linked polymer in the process of Besling because it is one of the most popular polymers used in the industry and because it is taught by Odian.

The limitations of claims 1, 4, 6, 10, 11, 12, and 13 have been addressed above and rejected for the same reasons, supra.

As to claim 2, Besling teaches using a porous dielectric material as the overlay material, making an organic polysilica (organosilanes) material obvious because it is a well-known dielectric material in device fabrication.

As to claim 5, see col. 4, lines 4-5.

As to claim 8, see Figures.

As to claim 9, Besling teaches using polymer including UV photoresist material may be used as sacrificial material, making curing the sacrificial material composition for forming the sacrificial material obvious.

The above-cited claims differ from the prior art by specifying well-known features (such as cross-linked polymers in claims 3 and 7) to the art of device fabrication. It is the examiner's position that a person having ordinary skill in the art at the time of the claimed invention would have found it obvious to modify the prior art by

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adding any of same well-known features to same in order to fabricate an easily removable sacrificial material layer with a reasonable expectation of success.

Claims 1-13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Babich et al. (US 6,815,329; hereinafter "Babich") in view of Odian (p.18, "Principles of Polymerization", 1981, second edition).

In a method of manufacturing a device, Babich teaches that a sacrificial material layer may be disposed on a device substrate. An overlayer (e.g., porous dielectric) material may be disposed on the sacrificial material layer. The sacrificial material layer may be removed to form an air gap. The sacrificial material layer may comprise a polymer (col. 8 and 9; Figures). Babich teaches using a polymer as sacrificial material. The disclosure of Babich is not limited to any type of polymer. In the book of "Principles of Polymerization", Odian teaches that polymers may be linear, branched, or cross-linked polymers (p.18). Hence, it would have been obvious to one with ordinary skill in the art to use a cross-linked polymer in the process of Babich because it is one of the most popular polymers used in the industry and because it is taught by Odian.

The limitations of claims 1, 4, 6, 10, 11, 12, and 13 have been addressed above and rejected for the same reasons, supra.

As to claim 2, Babich teaches using a porous dielectric material as the overlay material, making an organic polysilica (organosilanes) material obvious because it is a well-known dielectric material in device fabrication (col.9, lines 41-58.

As to claim 5, see col. 8, lines 64-66.

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As to claim 8, see Figures.

The above-cited claims differ from the prior art by specifying well-known features (such as cross-linked polymers in claims 3 and 7; applying and curing a cross-linkable polymer in claim 9) to the art of device fabrication. It is the examiner's position that a person having ordinary skill in the art at the time of the claimed invention would have found it obvious to modify the prior art by adding any of same well-known features to same in order to fabricate an easily removable sacrificial material layer with a reasonable expectation of success.

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Kin-Chan Chen whose telephone number is (571) 272-1461. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Kin-Chan Chen Primary Examiner

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